

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/720,966	11/24/2003	Tsing-Tang Song	250913-1030	5221
24504	7590 05/31/2006		EXAMINER	
THOMAS, KAYDEN, HORSTEMEYER & RISLEY, LLP			CHU, JOHN S Y	
100 GALLERIA PARKWAY, NW STE 1750		ART UNIT	PAPER NUMBER	
ATLANTA, (A 30339-5948		1752	
			DATE MAILED: 05/31/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

			;			
	Application No.	Applicant(s)				
Office Action Commence	10/720,966	SONG et al				
Office Action Summary	Examiner	Art Unit				
	John S. Chu	1752				
The MAILING DATE of this communication appeared for Reply	pears on the cover she	et with the correspondence a	ddress			
A SHORTENED STATUTORY PERIOD FOR REPI WHICHEVER IS LONGER, FROM THE MAILING [- Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMM .136(a). In no event, however, m d will apply and will expire SIX (6 te. cause the application to beco	UNICATION. hay a reply be timely filed) MONTHS from the mailing date of this me ABANDONED (35 U.S.C. § 133)				
Status						
1) Responsive to communication(s) filed on 13 I	<u> March 2006</u> .					
2a) This action is FINAL . 2b) ⊠ Thi	This action is FINAL . 2b)⊠ This action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under	Ex parte Quayle, 1935	C.D. 11, 453 O.G. 213.				
Disposition of Claims						
4) Claim(s) 1,2,6-11 and 14-19 is/are pending in 4a) Of the above claim(s) is/are withdra 5) Claim(s) is/are allowed. 6) Claim(s) 1,2,6-11 and 14-19 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/e	awn from consideration					
Application Papers						
9) The specification is objected to by the Examin 10) The drawing(s) filed on is/are: a) accomposite and applicant may not request that any objection to the Replacement drawing sheet(s) including the correct and the oath or declaration is objected to by the Examin	cepted or b) objected or by objected or by objected or about or or or by	eyance. See 37 CFR 1.85(a). wing(s) is objected to. See 37 C				
Priority under 35 U.S.C. § 119						
a) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureat * See the attached detailed Office action for a list	ats have been received. ats have been received ority documents have beau (PCT Rule 17.2(a)).	in Application No een received in this National	l Stage			
Attachment(s)						
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date	Paper 5) D Notice	iew Summary (PTO-413) No(s)/Mail Date e of Informal Patent Application (PTo :	O-152)			

Application/Control Number: 10/720,966

Art Unit: 1752

DETAILED ACTION

This Office action is in response to the amendment filed March 13, 2006.

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1, 2, 6-11, 14-19 are rejected under 35 U.S.C. 103(a) as being unpatentable over NOJIMA et al (6,399,277) in view of SCHULTA et al (6,306,555).

The claimed invention is drawn to the following:

 (Currently amended): A negative photoresist composition with multi-reaction systems, comprising the following components as a uniform solution in an organic solvent:

at least one seasoned or unsaturated resin having a molecular weight in the range from 5,000 to 250,000 and an acid value between 50 and 250mgKOH/g, selected from the group consisting of homopolymers, copolymers, and combinations thereof, which the homopolymers and the copolymers are synthesized by at least one monomer selected from the group consisting of styrene, methyl styrene scrylic acid, acrylate, methyl lacrylic acid, methyl acrylate, vinyl ether, and combinations thereof;

at least one photoinitiator in an amount of 0.1 to 35 parts by weight, based on 100 parts by weight of the saturated or unsaturated resin;

- at least one free radical reactive monomer in an amount of 0.1 to 100 parts by weight;
- at least one photoscid generator in an amount of 0.1 to 35 parts by weight; and
- at least one cation reactive monomer in an amount of 0.1 to 35 parts by weight.

NOJIMA et al discloses a photopolymerizable thermosetting resin composition comprising an unsaturated resin, a diluent (represented by an photopolymerizable vinyl type monomer), a photopolymerization initiator, a setting adhesion-imparting initiator (see column

Art Unit: 1752

12, line 63 – column 13, line 53 wherein lines 33-39, which disclose onium photoacid generating compounds), and an epoxy group-containing compound (meets the claimed cation reactive monomer). The compositional ingredients can be found in column 4, lines 26-34 wherein each of the components, which desired is disclosed.

NOJIMA et al lacks a working example with a photoacid generator. Here applicants are directed to column 13, lines 32-42 wherein suitable acid generators include triphenyl sulfonium hexafluoroantimonate and diphenyliodonium tetrafluoroborate for the photoacid generating compounds which are seen as functionally equivalent to the listed setting-adhesion imparting agents defined as component (D).

SCHULTZ et al discloses the functional equivalence of the triflate onium salts to the disclosed hexafluoroantimonate anions (column 41, lines 39-48) of NOJIMA et al such that the skilled artisan would reasonably expect same or similar results with using any of the known onium salt photoacid generators for cationic polymerization.

It would have been *prima facie* obvious to one of ordinary skill in the art of photopolymerizable thermosetting composition to insert a triphenylsulfonium triflate in for the triphenylsulfonium hexafluoroantimonate for the setting-adhesion imparting agent of dicyandiamide with the reasonable expectation of same or similar results for excellent properties for a solder resist like soldering resistance, solvent resistance, and chemical resistance.

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

Application/Control Number: 10/720,966

Art Unit: 1752

Page 4

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Cynthia Kelly, can be reached on (571) 272-1526

The fax phone number for the USPTO is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John S. Chu

Frimary Examiner, Group 1700

J.Chu May 26, 2006